PROVEN PARTICLE REDUCTION IN ALD & CVD PROCESSES



FLP 515 - STAINLESS STEEL FIBER MEDIA

Mott High Purity Filters provide 9-log filtration of particles down to 0.0015 µm resulting in particle-free gas. The FLP is designed for filtration of low vapor pressure, high temperature gases generated in a direct liquid injection system, where the process utilizes a vaporization chamber. FLP515 is ideal for filtering vapor phase low pressure dopants or organometallic precursor vapors such as TEMAZ, TEOS, TiCl4, TDMAT, TEPO, TEB, POCI, Z4MS, Ztomcats, Trans-LC, TMB, and others.



APPLICATIONS

The FLP is designed for filtration of low vapor pressure gases from a mixture of chemical precursor vapor liquid source volatile precursors, high temperature gases generated in a direct liquid injection system, where the process utilizes a vaporization chamber.

MATERIALS

» Hardware: 316L SS » Filter Medium: 316L SS

» Wetted Hardware Surface Finish: 5 Ra, Electro-polished

OPERATING CONDITIONS

- » Maximum Operating Pressure: 2500 psig (172.5 barg)
- » Maximum Operating Temperature for Inert Gas: 450°C
- » Maximum Differential Pressure: 500 psid (34.5 bar)

PROVEN RESULTS

Mott filters have been proven to perform in various semiconductor manufacturing environments, including but not limited to:

	Environment 1	Environment 2	Environment 3	Environment 4
Precursor Type	ZrO2	ZrO2	Hf02	CpZr(NMe2)3 & Sr-20
Process Type	ALD	ALD	CVD	ALD
Filter Model	FLP515FF33	FLP515FF33	FLP515FF33	FLP515FF33
Vaporizer	MSP	MSP	Horiba	TRIJET
Operating Temperature	150°C	150°C	150°C	150°C
Chamber Pressure (mTorr)	0.8~0.9	0.7~0.8	-	8
Carrier Gas Operating Pressure	15~24	15~24	15~24	15~24
Flow Rate (SLPM)	20.45	1.90	9.4	≤ 5 sccm
Process	High-K	High-K	High-K	ZYALD & SR-20
Uniformity (%)	~ ≤ 2	~ ≤ 2	~ ≤ 5	≤ 3
Particle Size (µm)	~0.08	~0.08	~0.14	~0.1
P/C (bare)	≤ 200	≤ 200	≤ 400	≤ 100
P/C (pattern)	≤ 20	≤ 20	≤ 400	Unknown